

### **REISSUE APPLICATION DECLARATION AND POWER OF ATTORNEY**

As the below named inventor, I hereby declare that: my residence, post office address and citizenship are as stated below my name; I believe I am an original, first inventor of the subject matter which is described and claimed in Letters Patent number 6,020,592 granted on February 1, 2000, and in the preliminary amendment filed April 17, 2001, and in the specification filed April 17, 2001, entitled DOSE MONITOR FOR PLASMA DOPING SYSTEM and for which invention I solicit a reissue patent.

### **ACKNOWLEDGEMENT OF REVIEW OF PAPERS AND DUTY OF CANDOR**

I hereby state that I have reviewed and understand the contents of the above-identified specification and preliminary amendment, including the claims.

I acknowledge the duty to disclose information which is material to the examination of this application in accordance with Title 37, Code of Federal Regulations § 1.56.

### **STATEMENT OF INOPERATIVENESS OF ORIGINAL PATENT** **37 CFR § 1.175**

I believe the original patent to be partly inoperative or invalid by reason of the patentee claiming less than patentee had a right to claim in U.S. Patent No. 6,020,592. For example, U.S. Patent No. 6,020,592 does not include a claim that recites “[a]n ion implantation system for causing ions to impact an implantation surface comprising: a) a process chamber defining a chamber interior into which one or more workpieces can be inserted for ion treatment; b) an energy source for setting up an ion plasma within the process chamber; c) a support for positioning one or more workpieces within an interior region of the process chamber so that an implantation surface of the one or more workpieces is positioned within the ion plasma; d) a pulse generator in electrical communication with the workpiece support for applying electrical pulses for attracting ions to the support; e) one or more dosimetry cups including an electrically biased ion collecting surface parallel to the implantation surface; and f) an implantation controller for monitoring signals from the one or more dosimetry cups to control ion implantation of the one or more workpieces.”

All errors in the present reissue application up to the time of signing this declaration, or errors which are being corrected by a paper filed concurrently with this declaration which correction of errors I have reviewed, arose without any deceptive intention on the part of the applicant.

### POWER OF ATTORNEY

I hereby revoke all prior appointments of attorneys and/or agents to prosecute this application and to transact all business in the Patent and Trademark Office connected therewith. I now hereby appoint the following attorneys and agents to prosecute this application and to transact all business in the Patent and Trademark Office connected therewith:

The undersigned hereby appoints the practitioners as defined by:

NAME	REGISTRATION NUMBER
Scott R. Faber, Esq.	48,380
Changhoon Choi, Esq.	56,798
Nathaniel Lucek, Esq.	60,766
David Hwang, Esq.	38,697
William R. McClellan, Esq.	29,409

Address all telephone calls to Changhoon Choi, Esq., at telephone number 978-282-5915.  
Address all correspondence to Customer Number: **59901**.

I hereby declare that all statements made herein of my knowledge are true and that all statements made on information and belief are believed to be true; and further, that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code, and that such willful false statements may jeopardize the validity of this application or any patent issued thereon.



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Date: 5/1/08

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Date: \_\_\_\_\_

**Matthew GOECKNER**  
Citizenship: United States  
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